SEMINAR NOTICE

Department of Physics and Engineering Physics
University of Saskatchewan

SPEAKER: Dr. Michael Bradley
Physics & Engineering Physics

TOPIC: Plasma & Ion Beam Physics for Materials Growth & Processing Applications

DATE: October 30th, 2018

TIME: 3:30-4:30 p.m.

PLACE: Physics 103

ABSTRACT:

Energetic ions in plasma systems can be used in a variety of thin film growth and materials processing applications. Because of the wide range of available parameters in the plasma parameter space, different plasma systems are required to operate in very different regimes of pressure, power, plasma density, etc. This talk will discuss some of the design considerations relevant to plasma systems for materials growth (generally higher pressure and lower ion energy) as well as post-growth processing (generally lower pressure and higher ion energy). Some new applications using the radiofrequency and microwave driven plasma systems in the U of S Plasma Physics Lab (PPL) will be discussed. In addition a new ion beam system has been constructed, with important applications in studies of optical materials; some new results obtained using this beamline will be presented.

Coffee and Cookies will be served in Physics lounge at 3:00 p.m. for those attending the seminar.